



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Customer Number: 20277

Robert John SOCHA, et al. : Confirmation Number: 2388

Serial No.: 10/756,829 : Group Art Unit: 1756

Filed: January 14, 2004 : Examiner: Not yet assigned

For: METHOD OF OPTICAL PROXIMITY CORRECTION DESIGN FOR CONTACT HOLE

MASK

INFORMATION DISCLOSURE STATEMENT

Mail Stop Information Disclosure Statement Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the Patent and Trademark Office is hereby directed to the references listed on the attached form PTO-1449. It is respectfully requested that the references be expressly considered during the prosecution of this application, and that the references be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed within three months of the U.S. filing date OR before the mailing date of a first Office Action on the merits. No certification or fee is required.

Each reference was first cited in a corresponding foreign application search report or office action and its relevance discussed therein. A copy of the foreign search report or office action, is attached for the Examiner's information.

10/756,829

Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

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Date: July 14, 2004

	TABLE	NEX.						SHEE	T 1 OF 1
INFC	CIT	AT	ON DISCLOSTION IN AN LICATION	SURE	ATTY. DOCKET NO. 55071-328		SERIAL NO. 10/756,829		
(PTO-1449)					APPLICANT Robert John SOCHA, et al.				
					FILING DATE January 14, 2004 GROUP [case_group_art]				
				U.S. PATENT	DOCUMENTS	•			
EXAMINER'S INITIALS	CITE NO.	Document Number Number-Kind Code2 (if Known)		Publication Date MM-DD-YYYY	Name of Patentee or Appli Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear			
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		<u> </u>	EP 1 202 119 A1	05/02/2002	ASML masktools Netherlands B.V.				
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			OTHER A	RT (Including Author,	Title, Date, Pertinent Pages, E	tc.)	-		
EXAMINER'S INITIALS CITE NO. Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.									
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^{*}EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

1 Applicant's unique citation designation number (optional). 2 Applicant is to place a check mark here if English language Translation is attached.